

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant	:	Hayashi et al.
Appl. No.	:	10/561,830
Filed	:	December 22, 2005
For	:	POSITIVE RESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN USING SAME
Examiner	:	Eoff, Anca
Group Art Unit	:	1795

**SUBMISSION WITH RCE****Mail Stop Amendment**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed **May 14, 2010**, please consider the following remarks:

**The listing of claims** begins on page 2 of this paper. No amendments have been made.

**Remarks/Arguments** begin on 4 of this paper.